

(12) INTERNATIONAL APPLICATION PUBLISHED UNDER THE PATENT COOPERATION TREATY (PCT)

(19) World Intellectual Property Organization
International Bureau



(43) International Publication Date
15 March 2012 (15.03.2012)

PCT

(10) International Publication Number
WO 2012/032466 A1

(51) International Patent Classification:
C09G 1/02 (2006.01) *A01N 51/00* (2006.01)
C09G 1/04 (2006.01)

(21) International Application Number:
PCT/IB2011/053891

(22) International Filing Date:
6 September 2011 (06.09.2011)

(25) Filing Language: English

(26) Publication Language: English

(30) Priority Data:
61/380,722 8 September 2010 (08.09.2010) US

(71) Applicant (for all designated States except US): **BASF SE** [DE/DE]; 67056 Ludwigshafen (DE).

(71) Applicant (for MN only): **BASF (CHINA) COMPANY LIMITED** [CN/CN]; 300 Jiangxinsha Road, Shanghai, 200137 (CN).

(72) Inventors; and

(75) Inventors/Applicants (for US only): **NOLLER, Bastian** [DE/DE]; Einhäuser Landstraße 50, 64653 Lorsch (DE). **FRANZ, Diana** [DE/DE]; Gärtnerstraße 41a, 67105 Schifferstadt (DE). **LI, Yuzhuo** [US/DE]; Wieblinger Weg 33/4, 69123 Heidelberg (DE). **USMAN IBRAHIM, Sheik Ansar** [IN/US]; 32 maple Street, Apt 11, Potsdam, New York 13676 (US). **PINDER, Harvey Wayne** [US/US]; 5766 N. Lincoln Ave #301, Chicago, Illinois 60659 (US). **VENKATARAMAN, Shyam Sundar** [IN/—]; Yuanhua Rd., Zhongli City, Taoyuan County 320 (TW).

(74) Common Representative: **BASF SE**; 67056 Ludwigshafen (DE).

(81) Designated States (unless otherwise indicated, for every kind of national protection available): AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CL, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PE, PG, PH, PL, PT, QA, RO, RS, RU, RW, SC, SD, SE, SG, SK, SL, SM, ST, SV, SY, TH, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW.

(84) Designated States (unless otherwise indicated, for every kind of regional protection available): ARIPO (BW, GH, GM, KE, LR, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European (AL, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MK, MT, NL, NO, PL, PT, RO, RS, SE, SI, SK, SM, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Published:

- with international search report (Art. 21(3))
- before the expiration of the time limit for amending the claims and to be republished in the event of receipt of amendments (Rule 48.2(h))

(54) Title: AQUEOUS POLISHING COMPOSITIONS CONTAINING N-SUBSTITUTED DIAZENIUM DIOXIDES AND/OR N'-HYDROXY-DIAZENIUM OXIDE SALTS

(57) Abstract: An aqueous polishing composition comprising (A) at least one water-soluble or water-dispersible compound selected from the group consisting of N-substituted diazenium dioxides and N'-hydroxy-diazenium oxide salts; and (B) at least one type of abrasive particles; the use of the compounds (A) for manufacturing electrical, mechanical and optical devices and a process for polishing substrate materials for electrical, mechanical and optical devices making use of the aqueous polishing composition.



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